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Application Number:	10591718				
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Customer Number:	23869				
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1	Information Disclosure Statement (IDS) Filed (SB/08)	1608-7_PCT-US_IDS_3-19-09. pdf	871143	no	4
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3	Foreign Reference	EP1505439.pdf	2060009	no	63		
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4	NPL Documents	Sato_article.pdf	1089917	no	20		
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7	NPL Documents	Supplementary_SR.pdf	186567	no	5		
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